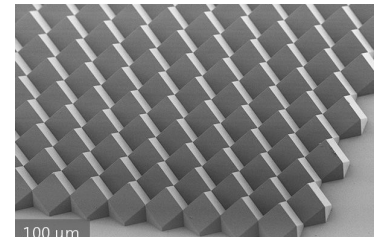
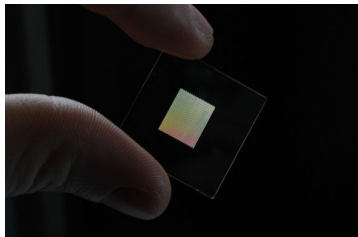
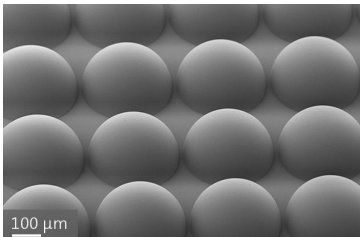


General introduction on 3D Laser Lithography

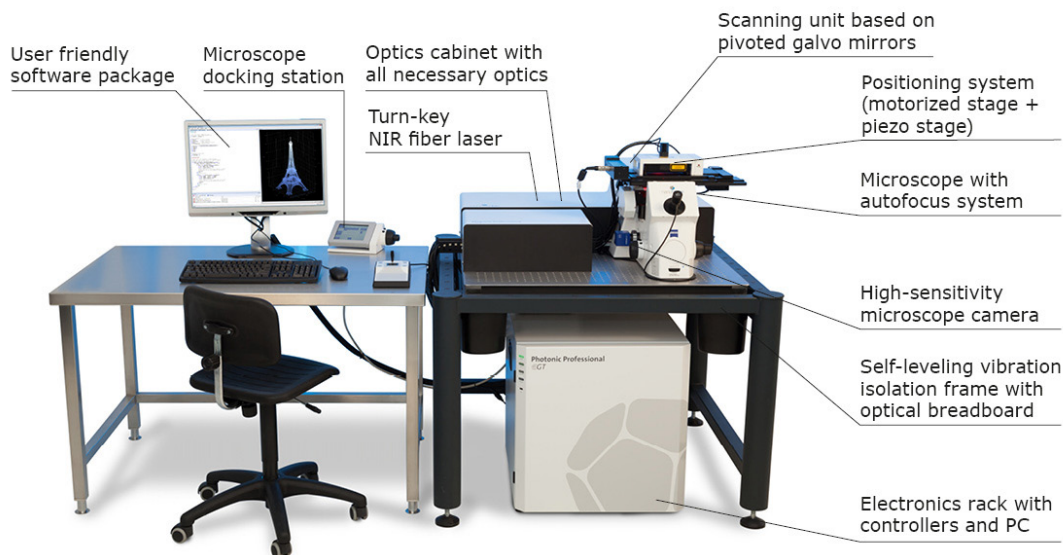
Beatrice Sartini - M.Sc.Eng., Nanoscribe Field Engineer

Tuesday, February 7, 2017 @ 1:00PM

Marcus Nanotechnology Building 1117-1118



Join us to learn from Nanoscribe engineers how the IEN's newest tool, the Photonic Professional GT 3D laser lithography system, can enhance and accelerate your lithography based research. The Nanoscribe 3D laser lithography system is ideal for those working in the fields of photonics and micro-optics, microelectromechanical systems (MEMS), microsystems and microfluidic components for regenerative medicine, cell biology and tissue engineering, multifunctional nanomaterials, as well as optical and mechanical metamaterials.



System Features:

- Highest resolution commercially available micro 3D printer
- High speed 3D printing by galvo technology
- Accurate and precise by piezo technology
- Two photon polymerization (2PP) of various UV-curable photoresists
- Two-photon lithography of common positive-tone photoresists
- Writing area up to 100 × 100 mm² range
- High-sensitivity microscope camera for realtime observation of the printing process
- User-friendly software package for 3D printing workflow
- Easy CAD import via STL file format